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PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM 10083991	FILING DATE 02/26/2002	CLASS 438	SUBCLASS 424	GAU 2812	EXAMINER ISRC
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**APPLICANTS: Chang Chia-Der; Yen Yi-Tung;

**CONTINUING DATA VERIFIED:

** FOREIGN APPLICATIONS VERIFIED:

PG-PUB	DO NOT PUBLISH <input checked="" type="checkbox"/>	RESCIND <input type="checkbox"/>
Foreign priority claimed 35 USC 119 conditions met		<input type="checkbox"/> yes <input checked="" type="checkbox"/> no
Verified and Acknowledged Examiner's initials		<i>Janetta L. Lee SPT</i>
ATTORNEY DOCKET NO TS01-660		
TITLE : Planarization method for deep sub micron shallow trench isolation process		
U.S. DEPT. OF COMM./PAT. & TM-PTO-436L(Rev. 12-94)		

NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED	
		Total Claims 10	Print Claim for O.G.
Assistant Examiner		DRAWING	
		Sheets Drwg.	Figs.Drwg.
ISSUE FEE		Print Fig.	
Amount Due	Date Paid		
TERMINAL		Primary Examiner	
DISCLAIMER		PREPARED FOR ISSUE	
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